

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): An exposure method of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus, comprising:

adjusting an image forming characteristic of a first exposure apparatus in said plurality of exposure apparatus to expose one layer in consideration of image distortion correction capability of a second exposure apparatus which is different from said first exposure apparatus; and

exposing another layer by using said second exposure apparatus after exposing the one layer by using the first exposure apparatus, wherein

the first exposure apparatus is a scanning type exposure apparatus and the second exposure apparatus is a stationary type exposure apparatus, and

the adjustment is performed so as to reduce an image distortion including a rectangular component or a parallelogrammatic component.

Claims 2-25 (Canceled)

Claim 26 (Original): A lithographic system of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus, comprising:

adjusting an image forming characteristic of a first exposure apparatus in said plurality of exposure apparatus to expose one layer, in accordance with information on image distortion correction capability of a second exposure apparatus which is different from said first exposure apparatus; and

exposing another layer by using said second exposure apparatus.

Claim 27 (Original): The lithographic system according to Claim 26, wherein said second exposure apparatus include at least one of

an exposure apparatus used in exposure for a previous layer which is exposed before exposure of said one layer by said one apparatus, and

an exposure apparatus used in exposure for a subsequent layer which is exposed after exposure of said one layer by said one apparatus.

Claim 28 (Original): The lithographic system according to Claim 27, further comprising a host computer for totally controlling said plurality of exposure apparatus, wherein

said host computer provides said first exposure apparatus with correction instructions on an optimum image forming characteristic which has been calculated in accordance with an image distortion characteristic of said second exposure apparatus.

Claim 29 (Original): The lithographic system according to Claim 28, wherein one of said first exposure apparatus and said second exposure apparatus is a stationary type exposure apparatus in which a mask and said substrate are almost stationary during exposure, and

the other of said first exposure apparatus and said second exposure apparatus is a scanning type exposure apparatus in which a mask and said substrate are moved synchronously during exposure.

Claim 30 (Original): A lithographic system of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus comprising:

a host computer for totally controlling said plurality of exposure apparatus; wherein said host computer respectively selects an exposure apparatus to be used for each layer from said plurality of exposure apparatus in accordance with the image distortion characteristics of said each exposure apparatus, and

said selected exposure apparatus adjusts its own image forming characteristic at the time of exposure in accordance with correction instructions from said host computer, said instructions on an optimum image forming characteristic of said selected apparatus.

Claim 31 (Original): A lithographic system comprising a first exposure apparatus and a second exposure apparatus, and forming patterns of a plurality of layers on a substrate using each of said exposure apparatus, wherein

said first exposure apparatus adjusts its own image forming characteristic, in consideration of an image distortion correction capability of said second exposure apparatus, and

said second exposure apparatus adjusts its own image forming characteristic, in consideration of an image distortion correction capability of said first exposure apparatus.

Claim 32 (Original): The lithographic system according to Claim 31, wherein one of said first and second exposure apparatus is a stationary type exposure apparatus in which a mask and said substrate are almost stationary during exposure, and the other of said first and second exposure apparatus is a scanning type exposure apparatus in which a mask and said substrate are moved synchronously during exposure.

Claim 33 (Original): The lithographic system according to Claim 32, wherein each of said stationary type exposure apparatus and said scanning type exposure apparatus corrects its own image distortion component which can be corrected upon exposure.

Claim 34 (Original): The lithographic system according to Claim 33, wherein said image distortion component which can be corrected include
at least one of a rectangular component and a parallelogrammatic component in said scanning type exposure apparatus, and
at least one of a trapezoidal component and an axially symmetrical image distortion component in said stationary type exposure apparatus.

Claim 35 (Original): The lithographic system according to Claim 32, wherein exposure is performed with each of said stationary type exposure apparatus and said scanning type exposure apparatus adjusting image forming characteristics such that
said one exposure apparatus of said stationary type and scanning type exposure apparatus roughly corrects an image distortion component which can be corrected by said other exposure apparatus, and
said one exposure apparatus of said stationary type and scanning type exposure apparatus finely adjusts an image distortion component which is difficult or impossible to be corrected by said other apparatus.

Claim 36 (Original): The lithographic system according to Claim 35, wherein said stationary type exposure apparatus roughly corrects
at least one image distortion components of a rectangular component and a parallelogrammatic component, and finely corrects

at least one image distortion component of a trapezoidal component and axially symmetrical image distortion component.

Claim 37 (Original): An exposure apparatus which exposes a substrate with an energy beam and transfers a predetermined pattern onto said substrate, comprising:

- a substrate stage for holding said substrate;
- an optical system through which said energy beam passes;
- an image forming characteristic correction mechanism for correcting a pattern image distortion which is transferred onto said substrate by said energy beam via said optical system; and

- a controller for controlling said image forming characteristic correction mechanism in consideration of an image distortion correction capability of another exposure apparatus used in a series of lithography processes.

Claim 38 (Original): The exposure apparatus according to Claim 37, which further comprises a mask stage to hold a mask, said pattern formed on said mask.

Claim 39 (Original): The exposure apparatus according to Claim 38, further comprising a driving unit which relatively scans said substrate stage holding said substrate and said mask stage holding said mask in a linear direction against said energy beam, wherein said controller further controls at least one of a relative scanning velocity ratio and an angle between scanning directions of said substrate stage and said mask stage through said driving unit, in consideration of an image distortion correction capability of said another exposure apparatus.

Claim 40 (Original): A method of making an exposure apparatus in which an energy beam exposes a substrate and transfers a predetermined pattern onto said substrate, comprising:

- providing a substrate stage for holding said substrate,
- providing an optical system through which said energy beam passes,
- providing an image forming characteristic correction mechanism for correcting a pattern image distortion which is transferred onto said substrate by said energy beam via said optical system; and

providing a controller for controlling said image forming characteristic correction mechanism in consideration of an image distortion correction capability of another exposure apparatus used in a series of lithography processes.

Claim 41 (Original): The method of making an exposure apparatus according to Claim 40, which further comprises providing a mask stage to hold a mask, said pattern formed on said mask.

Claim 42 (Original): The method of making an exposure apparatus according to Claim 41, further comprising:

providing a driving unit which scans said mask stage and said substrate stage in a linear direction against said energy beam, wherein

said driving unit can change at least one of a relative velocity ratio and an angle between said scanning directions of said mask stage and said substrate stage.

Claim 43 (Original): A device manufacturing method including a lithographic process, wherein exposure is performed using the method according to Claim 1 in said lithographic process.

Claims 44-48 (Canceled)

Claim 49 (Original): A device manufacturing method including a lithographic process, wherein the lithographic system according to Claim 26 is used in said lithographic process.

Claim 50 (Original): A device manufacturing method including a lithographic process, wherein the lithographic system according to Claim 30 is used in said lithographic process.

Claim 51 (Original): A device manufacturing method including a lithographic process, wherein the lithographic system according to Claim 31 is used in said lithographic process.

Claim 52 (New): The exposure method according to Claim 1, wherein the adjustment is performed so as not to reduce an image distortion including an axially symmetrical

component or a trapezoidal component which could be corrected by the second exposure apparatus.

Claim 53 (New): The exposure method according to Claim 52, wherein the first and second exposure apparatus are controlled by a host computer, the host computer selecting the first and second exposure apparatus based on the respective image distortion correction capabilities to expose the layers on the substrate.

Claim 54 (New): The exposure method according to Claim 1, wherein the first and second exposure apparatus are controlled by a host computer, the host computer selecting the first and second exposure apparatus based on the respective image distortion correction capabilities to expose the layers on the substrate.

Claim 55 (New): The exposure method according to Claim 54, wherein the host computer controls the adjustment of the image forming characteristic.

Claim 56 (New): An exposure method of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus, comprising:

adjusting an image forming characteristic of a first exposure apparatus in said plurality of exposure apparatus to expose one layer in consideration of image distortion correction capability of a second exposure apparatus which is different from said first exposure apparatus; and

exposing another layer by using said second exposure apparatus after exposing the one layer by using the first exposure apparatus; wherein

the first exposure apparatus is a stationary type exposure apparatus and the second exposure apparatus is a scanning type exposure apparatus, and

the adjustment is performed so as to reduce an image distortion including an axially symmetrical component or a trapezoidal component.

Claim 57 (New): The exposure method according to Claim 56, wherein the adjustment is performed so as not to reduce an image distortion including a rectangular component or a parallelogrammatic component which could be corrected by the second exposure apparatus.

Claim 58 (New): The exposure method according to Claim 57, wherein the first and second exposure apparatus are controlled by a host computer, the host computer selecting the first and second exposure apparatus based on the respective image distortion correction capabilities to expose the layers on the substrate.

Claim 59 (New): The exposure method according to Claim 56, wherein the first and second exposure apparatus are controlled by a host computer, the host computer selecting the first and second exposure apparatus based on the respective image distortion correction capabilities to expose the layers on the substrate.

Claim 60 (New): The exposure method according to Claim 59, wherein the host computer controls the adjustment of the image forming characteristic.

Claim 61 (New): A device manufacturing method including a lithographic process, wherein exposure is performed using the method according to Claim 56 in said lithographic process.